

## Accepted Manuscript

Title: TiN-buffered substrates for photoelectrochemical measurements of oxynitride thin films

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## Research highlights

- New model system for photoelectrochemical measurements of oxynitride thin films
- Oxynitride thin films with tunable crystalline quality and surface orientation
- Oxynitride film growth with high controllability of the nitrogen content
- Oxynitride film growth starting with a ceramic pellet of the pristine oxide

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